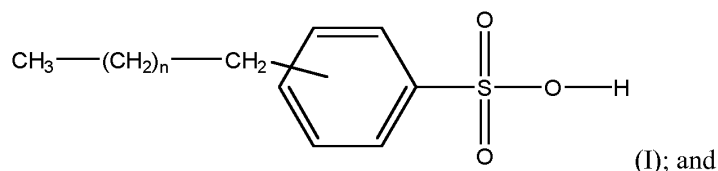


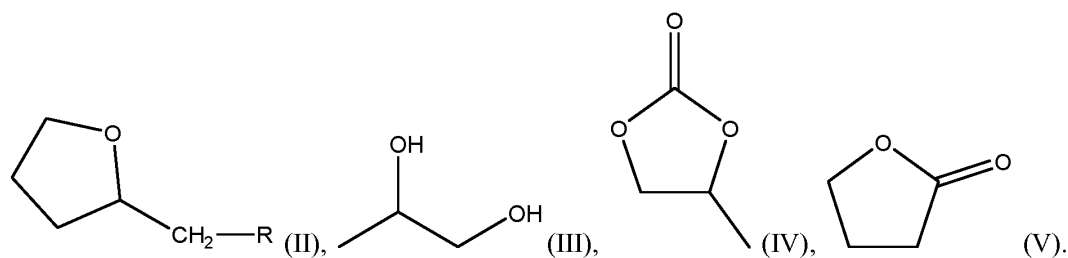
We claim:

1. A composition consisting essentially of

an alkylbenzenesulfonic acid having structure (I), wherein n is an integer from 0 to 16;

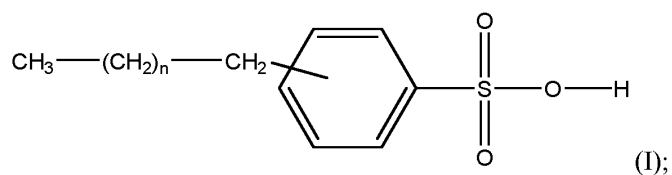


a solvent which is either selected from the group consisting of solvents having structures (II), (wherein R is selected from the group consisting of $-(\text{-O-CH}_2\text{-CH}_2\text{-})_n\text{-OH}$, -OH , and -O-C(=O)-CH_3 , wherein n' is equal to 1, 2, 3, or 4), a solvent having structure (III), a solvent having structure (IV), and a solvent having structure (V), or a solvent mixture, of at least two solvents selected from this group;



2. A composition consisting essentially of

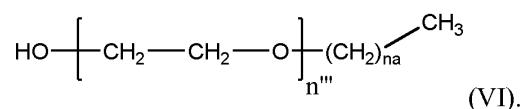
an alkylbenzenesulfonic acid selected having structure (I), wherein n is an integer from 0 to 16;



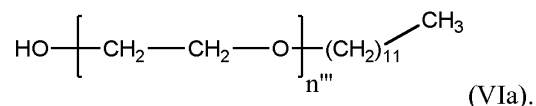
a solvent which is either selected from the group consisting of solvents having structures (II), (wherein R is selected from the group consisting of $-(\text{-O-CH}_2\text{-CH}_2\text{-})_n\text{-OH}$, -OH , -O-C(=O)-CH_3 , wherein n' is equal to 1, 2, 3, or 4), a solvent having structure (III), a solvent having structure (IV),

and a solvent having structure (V), or a solvent mixture, of at least two solvents selected from this group; and a surfactant.

3. The composition of claim 2, wherein the surfactant is a polymeric surfactant having structure (VI), wherein n''' is the number of polymer repeat unit and n_a is the number of CH_2 spacer moieties, wherein n_a is an integer from 8 to 14;



4. The composition of claim 3, wherein said polymeric surfactant has structure (VIa)

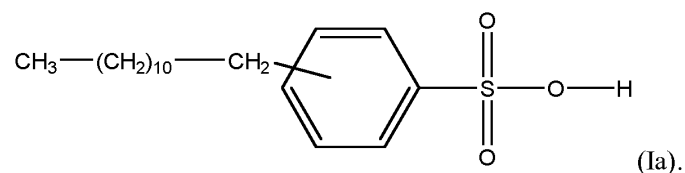


5. The composition of any one of claims 1 to 4, wherein for said alkylbenzenesulfonic acid n is an integer from 8 to 16.

6. The composition of any one of claims 1 to 5, wherein for said alkylbenzenesulfonic acid n is an integer from 8 to 14.

7. The composition of any one of claims 1 to 6, wherein for said alkylbenzenesulfonic acid n is an integer from 8 to 10.

8. The composition of any one of claims 1 to 7, wherein for said alkylbenzenesulfonic acid it has structure (Ia)

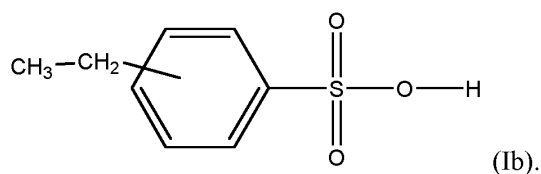


9. The composition according to any one of claims 1 to 4, wherein for said alkylbenzenesulfonic acid n is an integer from 0 to 10.

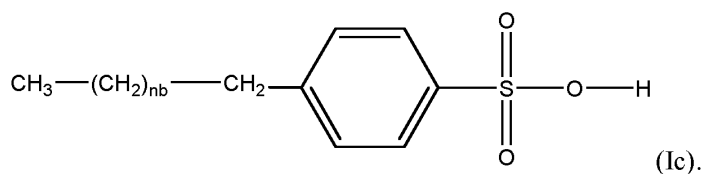
10. The composition according to any one of claims 1 to 4, wherein for said alkylbenzenesulfonic acid n is an integer from 0 to 5.

11. The composition according to any one of claims 1 to 4, wherein for said alkylbenzenesulfonic acid n is an integer from 0 to 2.

12. The composition according to any one of claims 1 to 4, wherein for said alkylbenzenesulfonic acid has structure (Ib);



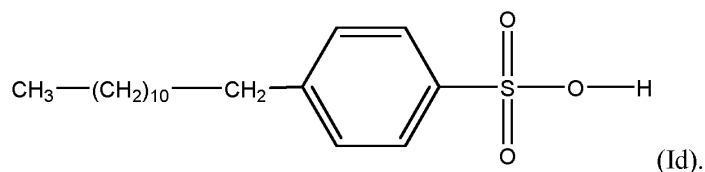
13. The composition according to any one of claims 1 to 4, wherein said alkylbenzenesulfonic acid has structure (Ic), wherein n_b is an integer from 0 to 16;



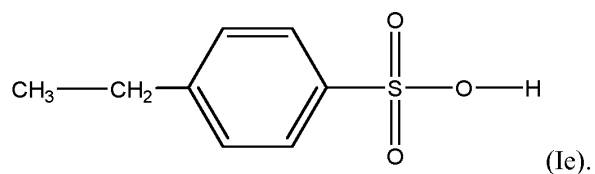
14. The composition of claim 13, wherein n_b is an integer from 10 to 14.

15. The composition of claims 13 or 14, wherein n_b is an integer from 8 to 10.

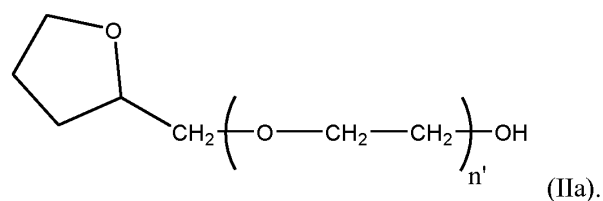
16. The composition of any one of claims 13 to 15, wherein said alkylbenzenesulfonic acid has structure (Id);



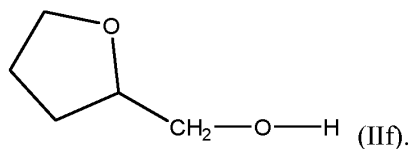
17. The composition of claim 13, wherein nb is an integer from 0 to 10.
18. The composition of claim 13, wherein nb is an integer from 0 to 5.
19. The composition of claim 13, wherein said alkylbenzenesulfonic acid has structure (Ie);



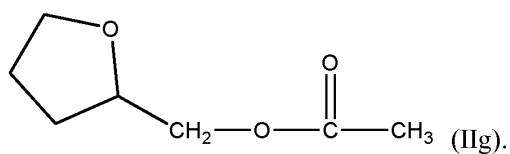
20. The composition according to any one of claims 1 to 19, wherein said solvent is a single solvent which has a structure falling within the scope of structures (II).
21. The composition according to any one of claims 1 to 19, wherein said solvent is a mixture of at least two different solvent having structure (II).
22. The composition according to any one of claims 1 to 19, wherein said solvent has structure (IIa), wherein n' is 1, 2, 3 or 4;



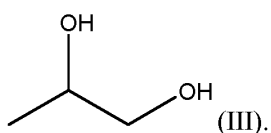
23. The composition according to any one of claims 1 to 19, wherein said solvent is a mixture of at least two solvents having structure (IIa) having different values of n' 1, 2, 3, or 4.



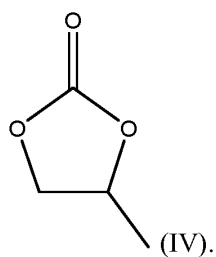
29. The composition according to any one of claims 1 to 19, wherein said solvent has structure (IIg);



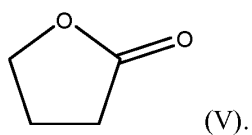
30. The composition according to any one of claims 1 to 19, wherein said solvent has structure (III);



31. The composition according to any one of claims 1 to 19, wherein said solvent has structure (IV);



32. The composition according to any one of claims 1 to 19, wherein said solvent has structure (V);



33. A process comprising the steps;
- i) heating the composition according to any one of claims 1 to 32, at a temperature which is from about room temperature to about 100°C;
 - ii) dipping a substrate coated with a patterned photoresist film into said heated composition for a time from about 1 minutes to about 60 minutes, until a dipped substrate with a removed photoresist film, results;
 - iii) after dipping step ii), rinsing said dipped substrate with a removed photoresist film with either isopropyl alcohol, water or a mixture of isopropyl alcohol and water to remove any residual composition from dipping step ii), producing a clean substrate;
 - iv) drying said clean substrate, by either spin drying it in air, or by using a stream of nitrogen or air to dry it.
34. The process of claim 33, wherein in step i) the composition is heated from about 60°C to about 100°C.
35. The process of claims 33 or 34, wherein in step ii), the substrate is a metal.
36. The process of any one of claims 33 to 35, wherein in step ii), the substrate is copper.
37. The process of any one of claims 33 to 36, wherein in step ii), the substrate is dipped from about 1 minute to about 5 minutes.
38. The process of any one of claims 33 to 37, wherein in step iii) the rinse is done with water.